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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO
10/807,052	03/22/2004	Hajime Shirakawa	P/1596-74	2685
2352 7	7590 10/19/2006		EXAMINER	
	K FABER GERB & S	ALANKO, ANITA KAREN		
	E OF THE AMERICAS NY 100368403		ART UNIT	PAPER NUMBER
			1765	
			DATE MAILED: 10/19/2006	5

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)			
Office Action Summers	10/807,052	SHIRAKAWA ET AL			
Office Action Summary	Examiner	Art Unit			
	Anita K. Alanko	1765			
The MAILING DATE of this communication Period for Reply	appears on the cover sheet w	ith the correspondence address			
A SHORTENED STATUTORY PERIOD FOR REWHICHEVER IS LONGER, FROM THE MAILING.  Extensions of time may be available under the provisions of 37 CF after SIX (6) MONTHS from the mailing date of this communication. If NO period for reply is specified above, the maximum statutory por Failure to reply within the set or extended period for reply will, by some Any reply received by the Office later than three months after the rearned patent term adjustment. See 37 CFR 1.704(b).	G DATE OF THIS COMMUNI FR 1.136(a). In no event, however, may a n. eriod will apply and will expire SIX (6) MOI statute, cause the application to become A	ICATION. reply be timely filed  NTHS from the mailing date of this communication. BANDONED (35 U.S.C. § 133).			
Status					
1) Responsive to communication(s) filed on §	3/7/06 amdt.				
	This action is non-final.				
· <u> </u>	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is				
closed in accordance with the practice und	der <i>Ex parte Quayle</i> , 1935 C.D	D. 11, 453 O.G. 213.			
Disposition of Claims					
4)⊠ Claim(s) <u>11-22</u> is/are pending in the applic	cation.	·			
4a) Of the above claim(s) is/are with					
5) Claim(s) is/are allowed.					
6)⊠ Claim(s) <u>11-22</u> is/are rejected.					
7) Claim(s) is/are objected to.					
8) Claim(s) are subject to restriction as	nd/or election requirement.				
Application Papers					
9) The specification is objected to by the Exar	miner.				
10) The drawing(s) filed on is/are: a)		by the Examiner.			
Applicant may not request that any objection to	the drawing(s) be held in abeya	nce. See 37 CFR 1.85(a).			
Replacement drawing sheet(s) including the co	orrection is required if the drawing	g(s) is objected to. See 37 CFR 1.121(d).			
11) The oath or declaration is objected to by th	e Examiner. Note the attache	d Office Action or form PTO-152.			
Priority under 35 U.S.C. § 119					
12)⊠ Acknowledgment is made of a claim for for	eign priority under 35 U.S.C.	§ 119(a)-(d) or (f).			
a)⊠ All b)□ Some * c)□ None of:					
<ol> <li>1. ☐ Certified copies of the priority documents.</li> </ol>	nents have been received.				
<ol><li>Certified copies of the priority document</li></ol>	nents have been received in A	Application No			
3. Copies of the certified copies of the	•	received in this National Stage			
application from the International Bu	, , , , , , , , , , , , , , , , , , , ,				
* See the attached detailed Office action for a	a list of the certified copies not	received.			
Attachment(s)					
Notice of References Cited (PTO-892)	4) Interview	Summary (PTO-413)			
Notice of Draftsperson's Patent Drawing Review (PTO-948)  Paper No(s)/Mail Date.					
<ul> <li>B) Information Disclosure Statement(s) (PTO-1449 or PTO/SI Paper No(s)/Mail Date</li> </ul>	B/08) 5) \( \bigcup \text{Notice of } \) 6) \( \bigcup \text{Other:} \)	Informal Patent Application (PTO-152)			
. app. 110(0)/1100		<u> </u>			

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## Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).

Claims 11-22 are rejected under 35 U.S.C. 103(a) as being unpatentable over Shekel, Hartman and Thompson (WO 2003/027647 A1) in view of JP 2001-189297.

Shekel discloses an apparatus comprising:

a treating tank for immersing the substrates in a treating liquid stored therein (page 25, lines 32-33);

a holding arm for holding the substrates (robotics, page 26, lines 10-11), said holding arm being movable to a treating position in said treating tank for immersing the substrates in the treating liquid;

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a storage device 130 (Fig.3A) which stores

(a) a relationship between use history, treating rate of the treating liquid (page 31, lines 25-26; page 32, line 4 – the relationship is the "connection" between the etch rate and spectra), and

(b) an up-to-date use history of the treating liquid (inherent since have real-time control, and multiple ages of baths are accounted for and used in the model, for example processed wafer history includes bath history, page 35, lines 3-4); and

a calculating device which derives a current treating rate from (a) and (b) (Fig.3B, step 340; see also page 23, lines 4-6: Shekel discloses to determine an etch rate of a substance based on the disappearance or appearance of the chemical (page 23, lines 4-6), which encompasses calculating a current treating rate.).

Shekel does not explicitly disclose that the holding arm is for holding the substrates in vertical posture. JP 2001-189297 teaches that holding substrate in vertical posture is a useful configuration (Fig.4, 7). It would have been obvious to one with ordinary skill in the art have the holding arm for holding the substrates in vertical posture in the apparatus of Shekel because JP 2001-189297 teaches that this is a useful way hold substrates when immersing in treatment baths.

Shekel does not disclose computing means for determining a corrected treating time by the equation cited in claim 11. Rather, Shekel uses the current treating rate to control the apparatus so that the treating rate stays within a predetermined range (page 40, lines 6-13). However, it would have been obvious to one with ordinary skill in the art, since Shekel determines the use history for a fresh portion of treating liquid, the etch time for a fresh portion

of treating liquid, and the use history for the current treating liquid, to use the equation cited to determine a corrected treating time because, since, as Shekel teaches, etchants get loaded with by-products with time and their etching rate slow with time, that the corrected time will be extended and therefore the simplest way to correct a known fresh etchant time is multiplication by a factor, which factor is obvious to be the relative etch rates of a fresh to current etch rate. It is obvious to use the cited equation since Shekel teaches that etchants slow with time, and to increase the yield it is obvious to extend the time so that the etchant may be more efficiently used.

In addition, as to the wherein clauses of claims 12-20, the apparatus of Shekel is capable of performing these functions and therefore these functions do not patentably distinguish the claimed invention.

As to claims 12-13, the apparatus of Shekel takes into account, at least, the treated number of substrates and type of substrates (page 33, lines 26-27).

As to claims 17-20, Shekel discloses hydrofluoric acid (page 31, line 29), however the bath is capable of holding phosphoric acid.

Claims 17-19 are rejected under 35 U.S.C. 103(a) as being unpatentable over Shekel, Hartman and Thompson (WO 2003/027647 A1) in view of JP 2001-189297 and Schnegg (US 4,971,654).

As to claims 17-20, Shekel discloses hydrofluoric acid (page 31, line 29), however the bath is capable of holding phosphoric acid. Schnegg teaches that phosphoric and hydrofluoric acids are useful acids for etching substrates (col.8, lines 21-26). It would have been obvious to

etchants for substrates.

one with ordinary skill in the art to have a treating liquid which comprises phosphoric acid and hydrofluoric acid in the apparatus of Shekel because Schnegg teaches that they are useful

### Response to Amendment

The rejection of claims 14-16 under 35 U.S.C. 112, second paragraph is withdrawn since claim 14 has been amended to cite a computing device.

Phan is no longer applied in the rejection. Claims 11-22 are rejected under 35 U.S.C. 103(a) as being unpatentable over Shekel, Hartman and Thompson (WO 2003/027647 A1) in view of JP 2001-189297.

Claims 17-19 are rejected under 35 U.S.C. 103(a) as being unpatentable over Shekel, Hartman and Thompson (WO 2003/027647 A1) in view of JP 2001-189297 and Schnegg (US 4,971,654).

#### Response to Arguments

Applicant's arguments filed 8/7/06 have been fully considered but they are not persuasive. Examiner acknowledges that Shekel does not disclose the cited corrected treating time, however it is obvious to one with ordinary skill in the art. Shekel teaches to determine all the separate parts of the equation (a use history, an updated use history and an etch time for a fresh batch). It is obvious to use the cited equation since, as described above, Shekel teaches that etchants slow with time, and to increase the yield it is obvious to extend the time so that the etchant may be more efficiently used.

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#### **Conclusion**

Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Anita K. Alanko whose telephone number is 571-272-1458. The examiner can normally be reached on Mon-Fri until 2:30 pm (Wed until 11:30).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine Norton can be reached on 571-272-1465. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Anita K. Alauleo Anita K. Alanko

**Primary Examiner** 

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